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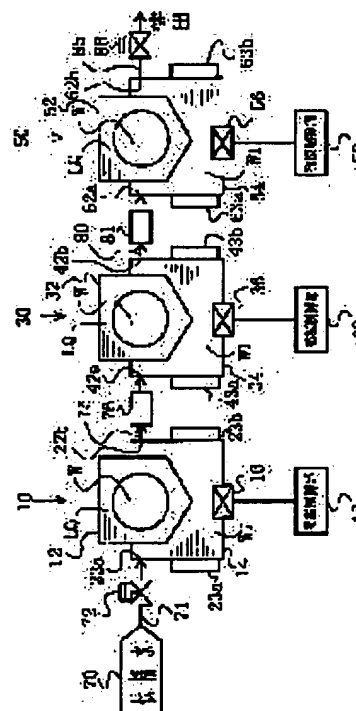
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(54) SUBSTRATE TREATING DEVICE

(57) Abstract:

PROBLEM TO BE SOLVED: To suppress a drop in the yield of a device by suppressing the occurrence of bubbles in running water and improving the treatment efficiency of the cleaning, etc., of a substrate.

SOLUTION: This substrate treating device is provided with a treating tank 10 in which treatment, such as cleaning, etc., is performed on a wafer W while the wafer W is dipped in a treating liquid LQ; an outer tank 14 which is arranged beside and under the tank 10, has a hermetically sealed structure, and contains the running water WT, and an ultrasonic vibrating body 16 which gives an ultrasonic wave to the treating liquid LQ contained in the tank 10 through the running water WT contained in the outer tank 14.



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